

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

| | | | |
|-----------------------|---|-------------------|----------------------|
| In re Application of: | Thomas Werner, et al | Examiner: | Daborah Chacko Davis |
| Serial No.: | 10/691,274 | Group Art Unit: | 1756 |
| Filed: | October 22, 2003 | Atty Docket: | 2000.105300 |
| | | Client Docket: | DE0302 |
| For: | Technique For Reducing Resist Poisoning In Forming A Metallization Layer Including A Low-K Dielectric | Confirmation No.: | 4933 |

RESPONSE TO FINAL OFFICE ACTION DATED AUGUST 20, 2007

Commissioner for Patents
P.O. Box 1450
Alexandria, VA 22313-1450

Sir:

This paper is submitted in response to the Office Action dated August 20, 2007 for which the three-month date for response is November 20, 2007. This response being filed less than two months from the mailing date of the action, Applicant is entitled to an Advisory Action. M.P.E.P. §706.07(f).

It is believed that no fee is due; however, should any fees under 37 C.F.R. §§ 1.16 to 1.21 be required for any reason, the Commissioner is authorized to deduct said fees from Williams, Morgan & Amerson, P.C. Deposit Account No. 50-0786/2000.105300.

Reconsideration of the application is respectfully requested.